

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Karola Richter et al.

JC20 Rec'd PCT/PTO 14 OCT 2003

Serial No:

Filing Date:

Title: SILICON SUBSTRATE COMPRISING POSITIVE ETCHING PROFILES
WITH A DEFINED SLOPE, ANGLE, AND PRODUCTION METHOD

Examiner:

Art Unit:

October 12, 2005

HMP201S1

**INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR § 1.97.****Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450****SIR:**

Applicants are respectfully submitting a copy of International Search Report dated November 17, 2004 and PCT SCHRIFTLICHER BESCHEID DER INTERNATIONALEN RECHERCHENBEHÖRDE issued by European Patent Office Berlin and copies of patent documents cited in the International Search Report of the instant application.

The following is a listing of the references in question.

- US 6 198 150
- US 6 180 466
- DE 197 36 370
- EP 0 822 582
- DE 42 41 045
- VOLLMAND et al., Dry etching with gas chopping without rippled sidewalls,
Journal of Vacuum Science & Technology , November 1999

10/553728

Applicants are respectfully submitting a form PTO-1449 with all references listed
therein and including citation in the application.

1020 Rec'd PCT/PTO 14 OCT 2001

The above recited references taken alone or in combination are believed neither
to anticipate or to render obvious the present application.

Consideration of the reference document during the examination of the present
application is respectfully requested.

Respectfully submitted,
Karola Richter et al.

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Reg. No. 28,559; Docket No.: HMP201

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

(2-92)

Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use separate sheets if necessary)</i>	Document Number (Patent) HMP 201	Application Number 507555728
	Assignee: RICHTER et al	
	Filing Date	Group Art Unit

U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

H.v. Boeing, FUNDAMENTALS OF PLASMA CHEMISTRY AND TECHNOLOGY
p. 174, The Research Institute of Plasma Chemistry, Carlsbad, CA
J. W. RANGELOW et al.; J. VAC. SCI. TECHNOL., B 13(6)
Nov/Dec 1995, pp 2394-2399
K. M. CHANG et al; JOURNAL OF APPLIED PHYSICS,
SEPT 1, 1996, VOL. 80, ISSUE 5, pp 3048-3055

EXAMINER

DATE COMPLETED

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